



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Re Reissue Application of :
 Tomowaki TAKAHASHI :
 Serial No.: 09/659,375 : Group Art Unit: 2872
 Filed: September 8, 2000 : Examiner: J. Henry
 For: **CATADIOPTRIC PROJECTION SYSTEMS**

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Simamiller
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AMENDMENT

Assistant Commissioner for Patents
 Washington, D.C. 20231

Sir:

This is responsive to the Final Office Action mailed May 29, 2001, having a shortened period for response set to expire on August 29, 2001. A petition and fee for a one-month Extension of Time is enclosed, thereby extending the response period to September 29, 2001.

The following amendment and remarks are respectfully submitted.

IN THE CLAIMS:

Please **ADD** new claim 58, as follows:

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58. (NEW) A method for projecting a pattern from a reticle onto a substrate, comprising:
 transmitting light from the reticle through a first imaging system, where the transmitted light pass through a singlepass lens group and a double-pass lens group to a concave mirror, and the light is reflected from the concave mirror back through the double-pass lens group toward the single-pass lens group;
 separating the light propagating through the doublepass lens group to the concave mirror from the light propagating through the double-pass lens group from the concave mirror;